IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant:	Hanson)
For:	SEMICONDUCTOR PROCESSING WORKPIECE SUPPORT WITH SENSORY SUBSYSTEM FOR DETECTION OF WAFERS OR OTHER SEMICONDUCTOR WORKPIECES))))))))
Serial No.:	Unassigned))
Filed:	Herewith)
Examiner:	Unassigned)
Art Unit:	Unassigned	

PRELIMINARY AMENDMENT

Commissioner of Patents Washington, D.C. 20231

Dear Sir:

Please amend the patent application filed concurrently herewith in the following manner prior to calculating the filing fee and prior to substantive examination of the application.

IN THE TITLE:

Please amend the title to read as follows:

"PROCESSING APPARATUS WITH SENSORY SUBSYSTEM FOR DETECTING THE PRESENCE/ABSENCE OF WAFERS OR OTHER WORKPIECES"

IN THE CLAIMS:

Please cancel claims 1-16 and add the following new claims 17-30.

- 17. (New) An apparatus for processing a workpiece of the type used in manufacturing microelectronic components, the apparatus comprising:
- a processing container adapted to hold a processing fluid used to process the workpiece;
- a workpiece holder for holding the workpiece in a processing position with respect to the processing container during processing;
- an electronic workpiece detection system providing an output signal indicative of the presence and absence of a workpiece on the workpiece holder;
- a control system for executing workpiece handling operations in response to the output signal received from the electronic workpiece detection system.
 - 18. (New) The apparatus of claim 17 wherein the control system executes operational safeguards to prevent mishandling of a workpiece in response to the output signal of the electronic workpiece detection system after the apparatus has experienced a power interruption.

- 19. (New) The apparatus of claim 17 wherein the electronic workpiece detection system comprises:
- an electromagnetic energy emitter for emitting electromagnetic energy in a direction for reflection by a workpiece held by the workpiece holder when a workpiece is present on the workpiece holder;
- an electromagnetic energy detector for detecting the presence of reflected electromagnetic energy indicative of the presence of a workpiece held by the workpiece holder.
 - 20. (New) The apparatus of claim 19 wherein said electronic workpiece detection system provides an output signal indicative of the presence of a workpiece based on the angle at which reflected electromagnetic energy is received by the electromagnetic energy detector.
 - 21. (New) The apparatus of claim 17 wherein the processing container and workpiece holder are adapted to electroplate the workpiece.

- 22. (New) An apparatus for processing a workpiece of the type used in manufacturing microelectronic components, the apparatus comprising:
- a plurality of workpiece supports and corresponding processing bases each defining a processing station;
- an electronic workpiece detection system for detecting the presence and absence of a workpiece at each of the processing stations;
- a control system for executing workpiece handling operations in response to the electronic workpiece detection system.
 - 23. (New) The apparatus of claim 22 wherein the control system executes operational safeguards to prevent mishandling of workpieces in response to the electronic workpiece detection system after the apparatus has experienced a power interruption.
 - 24. (New) The apparatus of claim 22 wherein at least one of the plurality of processing stations is adapted to electroplate a workpiece.
 - 25. (New) An apparatus for processing a workpiece of the type used in manufacturing microelectronic components, the apparatus comprising:
- a plurality of workpiece processing stations, each processing station including a workpiece holder for holding a workpiece,
 - a processing base adapted to receive a processing fluid used to process the workpiece,
 the workpiece holder and processing base being movable relative to one
 another between a first position in which a workpiece is loaded to or removed
 from the processing station and a second position in which the workpiece

holder is proximate the processing base for processing of a workpiece held thereby, and

an electronic workpiece detection system providing an output signal indicative of the presence and absence of a workpiece on the workpiece holder;

a control system for executing workpiece handling operations in response to the output signals received from the electronic workpiece detection systems.

- 26. (New) The apparatus of claim 25 wherein the control system executes operational safeguards to prevent mishandling of a workpiece in response to the output signal of the electronic workpiece detection system after the apparatus has experienced a power interruption.
- 27. (New) The apparatus of claim 25 wherein the electronic workpiece detection system comprises:
- an electromagnetic energy emitter for emitting electromagnetic energy in a direction for reflection by a workpiece held by the workpiece holder when a workpiece is present on the workpiece holder;
- an electromagnetic energy detector for detecting the presence of reflected electromagnetic energy indicative of the presence of a workpiece held by the workpiece holder.
 - 28. (New) The apparatus of claim 27 wherein said electronic workpiece detection system provides an output signal indicative of the presence of a workpiece based on the angle at

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which reflected electromagnetic energy is received by the electromagnetic energy detector.

- 29. (New) The apparatus of claim 27 wherein at least one of the plurality of processing stations is adapted to electroplate a workpiece.
- 30. (New) An apparatus for processing a workpiece of the type used in manufacturing microelectronic components, the apparatus comprising:

electrolytic deposition means for depositing a metal onto a surface of the workpiece;
workpiece detection means for detecting the presence and absence of a workpiece at the
electrolytic deposition means; and

control means for controlling handling of wafers in the apparatus in response to the workpiece detection means.

Respectfully submitted,

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